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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of

George et al

Serial No: 10/803,453

Filed: March 18, 2004

For: SLOTTED ELECTROSTATIC SHIELD MODIFICATION)
FOR IMPROVED ETCH AND CVD PROCESS
UNIFORMITY



Examiner: Not Yet Assigned

Art Unit: 2821

Attorney Docket: MAT-8

Date: August 2, 2004

CERTIFICATE OF MAILING I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner of Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on August 2, 2004.

Signed:

Jay R Beyer

Commissioner of Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

Enclosed is a copy of Information Disclosure Citation Form PTO-1449 together with copies of the non US patent documents cited on that form. It is respectfully requested that the cited documents be considered and that the enclosed copy of Information Disclosure Citation Form PTO-1449 be initialed by the Examiner to indicate such consideration and a copy thereof returned to applicant(s).

Pursuant to 37 C.F.R. § 1.97, the submission of this Information Disclosure Statement is not to be construed as a representation that a search has been made and is not to be construed as an admission that the information cited in this statement is material to patentability.

Pursuant to 37 C.F.R. § 1.97, this Information Disclosure Statement is being submitted under one of the following (as indicated by an "X" to the left of the appropriate paragraph):

X 37 C.F.R. §1.97(b).

37 C.F.R. §1.97(c). If so, then enclosed with this Information Disclosure Statement is one of the following:

A certification pursuant to 37 C.F.R. §1.97(e) or

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(1) A certification pursuant to 37 C.F.R. §1.97(e);

(2) A petition requesting consideration of the Information Disclosure Statement; and

(3) Please charge Deposit Account No. 19-1685 (Order No. MAT-8) \$___ for the fee under 37

C.F.R. §1.17(i) for submission of the Information Disclosure Statement. (a duplicate copy of this sheet is enclosed)

If there are any additional charges, please charge Deposit Account No. 19-1685 (Order No. MAT-8).

Respectfully submitted,

Jay R Beyer

Registration No. 39,907

Form 1449 (Modified)

Information Disclosure
Statement By Applicant

(Use Several Sheets if Necessary)

AUG 04 2004

Atty Docket No.

MAT-8

Applicants:

George, et al

Filing Date

March 18, 2004

Serial No.:

10/803,453

Group

2821

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
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	2	4,252,608	2/24/1981	Baldwin et al			
	3	4,358,686	11/9/1982	Kinoshita			
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Other Documents

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Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	1	Cicala et al., "Effect of Modulation on the Plasma Deposition of Hydrogenated and Fluorinated Silicon Nitride," 1990, Plasma-surface Interactions and Processing of Materials, pp. 171-173, NATO ASI Series E: Applied Sciences, vol. 176, Kluwer Academic Publishers, the Netherlands
	2	Cook et al., "Energy Anomalies Observed in Ion Beams Produced by rf Sources," Jun. 1962, The Review of Scientific Instruments, vol. 33, No. 6, pp. 649-652.
	3	Williams, "Extraction of Positive Ions from Electrodeless Discharge," Sep. 1966, The Review of Scientific Instruments, vol. 37, No. 9, pp. 1205-1210.
	4	Letts, S. L. et al., "Laser Program Annual Report-1978," vol. 1, Lawrence Livermore Report UCRL-50021-78, pp. 4-7 to 4-11.
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	8	Flamm, Letter from D. L. Flamm to B. S. Schneider dated Jul. 8, 1989.
	9	Manza, Letter from August Manza to B. S. Schneider dated Sep. 12, 1989.
	10	Flamm, Letter from D. L. Flamm to A. Manza dated Jun. 18, 1990.
	11	Turban, "Plasma Physics--Study of the electron temperature and density of an inductive HF discharge in hydrogen, using the symmetrical double-probe method", Sep. 27, 1971, C.R. Acad. Sc. Paris, vol. 273, Series B, pp 533-536. Both the French article and English translation of the text are included.
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	14	Weynants et al., "ICRH Antenna Design And Coupling Optimization Studies", 1980, Proceedings of the 2nd Joint Grenoble-Vienna International Symposium, vol. 1 (Como, Italy).
	15	Thornton, "Plasma-Assisted Deposition Processes: Theory, Mechanisms and Applications", 1983, Thin Solid Films, vol. 107, pp. 3-19.
	16	Probyn, "Sputtering of Insulators in an RF Discharge", 1968, Vacuum, vol. 18, No. 5, pp. 253-257.
	17	Sugano, "Applications of Plasma Processes to VLSI Technology", 1985, pp. 209 and 213.
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	19	Flamm et al., "The Design of Plasma Etchants", 1981, Plasma Chemistry and Plasma Processing, vol. 1, No. 4, pp. 317-363.

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	21	Coburn et al., "Positive-ion bombardment of substrates in rf diode glow discharge sputtering", Dec. 1972, J. Appl. Phys. vol. 43, No. 12, pp. 4965-4971.
	22	Freisinger et al., "The neutral particle injectors RIG for fusion reactors", 1984, Atomkernenergie Kerntechnik, vol. 44 No. 1, pp. 81-86.
	23	Vossen, "Glow Discharge Phenomena in Plasma Etching and Plasma Deposition", Feb. 1979, J. Electrochem Soc., vol. 126, No. 2, pp. 319-324.
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

